



Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 18239-023US1	Application No. 10/597,806
		Applicant Bernhard Kneer et al.	
		Filing Date August 8, 2006	Group Art Unit 3722

Information Disclosure Statement
by Applicant
(Use several sheets if necessary)

(37 CFR §1.98(b))

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	2005/0248856	11/2005	Omura et al.			
	AB	2003/174408	9/8/2003	Rostalski Hans-Juergen et al.			
	AC	2004/0109237	6/10/2004	Epple et al.			
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	AF	2005/0219707	10/6/2005	Schuster et al.			
	AG	2005/0225737	10/13/2005	Weissenreider et al.			
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	AI	2005/0190455	9/1/2005	Rostalski et al.			
	AJ	2005/0179877	8/18/2005	Mulkens et al.			
	AK	2003/0174408	9/18/2003	Rostalski et al.			
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	AO	2005/0068499	3/31/2005	Docdoc et al.			
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Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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	ACC	7,187,503	03/06/2007	Rostalski et al.			
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	AEE	2007/0091451	04/26/2007	Schuster			
	AFF	2007/0109659	05/17/2007	Rostalski et al.			
	AGG	2006/0221456	10/05/2006	Shafer et al.			
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	AJJ	2006/0066962	03/30/06	Totzeck et al.			
	AKK	2005/0190435	09/01/2005	Shafer et al.			

Foreign Patent Documents or Published Foreign Patent Applications

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							Yes	No
	ALL	EP0291596	1/19/1994	EPO				
	AMM	WO 2005/059617	6/30/2005	WIPO				
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	AOO	WO 2005/006026	1/20/2005	WIPO				
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	AUU	EP 1522894	4/13/2005	EPO				
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	AYY	DD 224448	7/3/1985	Germany				

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Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AZZ	EP 1420302	5/19/2004	EPO				
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	ADDD	JP10-303114	11/13/1998	Japan				
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	AGGG	EP 1 489 462	12/22/2004	EPO				
	AHHH	EP 1 630 616	03/01/2006	EPO				

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	AJJJ	Dammel et al., "193 nm Immersion Lithography – Taking the Plunge", Journal of Photopolymer Science and Technology, vol. 17 no. 4, pp 587-607 (2004).
	AKKK	Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
	ALLL	Owa et al., "Immersion Lithography; its Potential Performance Issues", Proceeding of the SPIE, SPIE, Bellingham, VA, vol. 5040 no. 1, February 28, 2003, pp 724-733.
	AMMM	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, Vol. 17, No. 6, November 1999 (199-11) pp 3306-3309.
	ANNN	Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf , (January 28, 2004).

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